

Epidermal Balance / Skin Energy

ID	FACE Care / 700260.0001	ID-No: 001.001
pH-value	---	
Appearance	White cream	
Product Form	Emulsion W/O	
Claims	Anti-Ageing; Protecting; Caring; Microplastic-free	

St	Substance	INCI Name USA	% w/w	Manufacturer
1	Dermofeel Toco 70 non-GMO	Tocopherol, Helianthus Annuus (Sunflower) Seed Oil	0.25	Evonik, DE
	Verstabil PC	Phenoxyethanol, Caprylyl Glycol	1.00	Evonik, DE
	Dermofeel PGPR	Polyglyceryl-3 Polyricinoleate	2.50	Evonik, DE
	Tego SMO V	Sorbitan Oleate	2.50	Evonik, DE
	Magnesium Stearate	Magnesium Stearate	1.00	several
	Cutina HR	Hydrogenated Castor Oil	2.00	BASF, DE
	Tegosoft DEC	Diethylhexyl Carbonate	4.00	Evonik, DE
	Tegosoft OS	Ethylhexyl Stearate	18.00	Evonik, DE
	Keltrol CG-SFT	Xanthan Gum	0.20	CP Kelco, US
2	Water demin.	Water	60.15	several
	Glycerin 85%	Glycerin, Water	4.00	several
	Ajidew ZN-100	Zinc PCA	1.00	Ajinomoto, JP
3	REFORCYL®	Glycerin, Water, Glutamine, Decyl Glucoside, Phenethyl Alcohol, Citric Acid, Cistus Incanus Flower/Leaf/Stem Extract, Gynostemma Pentaphyllum Leaf/Stem Extract	3.00	RAHN AG, CH
4	White Poetry	Fragrance	0.40	Aromatic Flavours & Fragrances Europe Ltd., GB

Production

Heat 1 to 80°C while stirring / Heat 2 to 80°C while stirring / Add 2 very slowly to 1 while stirring, homogenise strongly / Cool to 40°C while stirring / Add 3 and 4 separately and cool to 20°C while stirring / Homogenise strongly.

Stability: Stable for more than 3 months at 5°, 25°, 40°C

Microbiological Stability: ---

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